



Docket No.: 6301/Consilium/DV

#8/11-4-02
PATENT/OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Badri N. KRISHNAMURTHY et al.

Serial No. 09/928,474

Filed: August 14, 2001

For: EXPERIMENT MANAGEMENT SYSTEM, METHOD AND MEDIUM

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

:

Group Art Unit: 2171

Examiner:

RECEIVED
OCT -4 2002
TECHNOLOGY CENTER 2800

RECEIVED
SEP 20 2002
Technology Center 2100

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right


Serial No. 09/928,474

to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,


HALE AND DORR LLP

A handwritten signature in black ink, appearing to read "Scott Alter", written over the printed name.

Scott M. Alter

Registration No. 32,879

1455 Pennsylvania Avenue, NW
Washington, DC 20004
TEL 202.942.8428 SMA:lrr
FAX 202.942.8484
Date: 9/19/02

INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (PTO-1449)				ATTY. DOCKET NO. 6301/Consilium/DV		SERIAL NO. 09/928,474 RECEIVED SEP 20 2002	
				APPLICANT Technology Center 2100 Badri N. KRISHNAMURTHY et al.			
				FILING DATE August 14, 2001		GROUP 2171	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
	4,698,766	10/06/87	Entwistle et al.			05/17/85	
	4,967,381	10/30/90	Lane et al.			07/06/89	
	5,208,765	05/04/93	Turnbull			07/20/90	
	5,226,118	07/06/93	Baker et al.			01/29/91	
	5,231,585	07/27/93	Kobayashi et al.			06/20/90	
	5,420,796	05/30/95	Weling et al.			12/23/93	
	5,469,361	11/21/95	Moyne			06/06/94	
	5,525,808	06/11/96	Irie et al.			12/20/94	
	5,586,039	12/17/96	Hirsch et al.			02/27/95	
	5,603,707	02/18/97	Trombetta et al.			11/28/95	
	5,664,987	09/09/97	Renteln			09/04/96	
	5,812,407	09/22/98	Sato et al.			08/12/97	
	5,828,778	10/27/98	Hagi et al.			06/12/96	
	5,832,224	11/03/98	Fehskens et al.			06/14/96	
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	61-171147	08/01/86	Japan				X
	6-184434	07/05/94	Japan				X
	0 621 522 A2	10/26/94	Europe			X	
	8-50161	02/20/96	Japan				X
	8-304023	11/22/96	Japan				X
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
February 1984. "Method and Apparatus of in Situ Measurement and Overlay Error Analysis for Correcting Step and Repeat Lithographic Cameras." <i>IBM Technical Disclosure Bulletin</i> , pp. 4855-4859.							
October 1984. "Method to Characterize the Stability of a Step and Repeat Lithographic System." <i>IBM Technical Disclosure Bulletin</i> , pp. 2857-2860.							
EXAMINER				DATE CONSIDERED			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

**INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION**



(PTO-1449)

ATTY. DOCKET NO.
6301/Consilium/DV

SERIAL NO.
09/928,474

RECEIVED**SEP 20 2002**

Technology Center 2100

APPLICANT
Badri N. KRISHNAMURTHY et al.

FILING DATE
August 14, 2001

GROUP
2171

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,859,964	01/12/99	Wang et al.			10/25/96
	5,863,807	01/26/99	Jang et al.			03/15/96
	5,870,306	02/09/99	Harada			06/13/97
	5,903,455	05/11/99	Sharpe, Jr. et al.			12/12/96
	5,916,016	06/29/99	Bothra			10/23/97
	5,923,553	07/13/99	Yi			10/05/96
	5,930,138	07/27/99	Lin et al.			09/10/97
	5,940,300	08/17/99	Ozaki			05/08/97
	5,960,214	09/28/99	Sharpe, Jr. et al.			12/04/96
	5,963,881	10/05/99	Kahn et al.			10/20/97
	5,982,920	11/09/99	Tobin, Jr. et al.			01/08/97
	6,041,270	03/21/00	Steffan et al.			12/05/97
	6,078,845	06/20/00	Friedman			11/25/96
	6,112,130	08/29/00	Fukuda et al.			10/01/97
	6,148,246	11/14/00	Kawazome			06/10/98

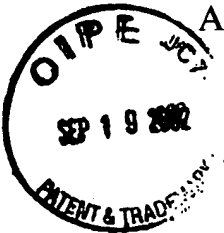
FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	0 747 795 A2	12/11/96	Europe			X	
	10-173029	06/26/98	Japan				X
	0 895 145 A1	02/03/99	Europe			X	
	11-126816	05/11/99	Japan				X

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	Schmid, Hans Albrecht. 1995. "Creating the Architecture of a Manufacturing Framework by Design Patterns." Austin, Texas: OOPSLA.
	Baliga, John. July 1999. "Advanced Process Control: Soon to be a Must." Cahners Semiconductor International. www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp
EXAMINER	DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 6301/Consilium/DV		SERIAL NO. 09/928,474 <div style="text-align: center; border: 1px solid black; padding: 5px;"> RECEIVED SEP 20 2002 </div>	
				APPLICANT Badri N. KRISHNAMURTHY et al. Technology Center 2100			
				FILING DATE August 14, 2001		GROUP 2171	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
	6,175,777	01/16/01	Kim			01/16/98	
	6,178,390	01/23/01	Jun			09/08/98	
	6,185,324	02/06/01	Ishihara et al.			01/31/95	
	6,192,291	02/20/01	Kwon			10/08/98	
	6,197,604	03/06/01	Miller et al.			10/01/98	
	6,211,094	04/03/01	Jun et al.			08/23/99	
	6,226,792	05/01/01	Goiffon et al.			10/14/98	
	6,230,069	05/08/01	Campbell et al.			06/26/98	
	6,236,903	05/22/01	Kim et al.			09/25/98	
	6,240,330	05/29/01	Kurtzberg et al.			05/28/97	
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	11-135601	05/21/99	Japan				X
	WO 00/05759	02/03/00	WO			X	
	WO 00/35063	06/15/00	WO			X	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
	July 5, 2001. "Motorola and Advanced Micro Devices Buy ObjectSpace Catalyst Advanced Process Control Product for Five Wafer Fabs." Semiconductor FABTECH. www.semiconductorfabtech.com/industry.news/9907/20.07.shtml						
	October 15, 2001. Search Report prepared by the Austrian Patent Office for Singapore Patent Application No. 200004286-1.						
	Johnson, Bob. June 10, 2002. "Advanced Process Control Key to Moore's Law." Gartner, Inc.						
	July 9, 2002. International Search Report prepared by the European Patent Office for PCT/US01/24910.						
	July 29, 2002. International Search Report prepared by the European Patent Office for PCT/US01/27407.						
	Sonderman, Thomas. 2002. "APC as a Competitive Manufacturing Technology: AMD's Vision for 300mm." AEC/APC.						
EXAMINER				DATE CONSIDERED			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 6301/Consilium/DV		SERIAL NO. 09/928,474 RECEIVED SEP 20 2002 Technology Center 2100	
				APPLICANT Badri N. KRISHNAMURTHY et al.			
				FILING DATE August 14, 2001		GROUP 2171	

OIPE JG
SEP 19 2002
PATENT & TRADEMARK OFFICE

U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	6,240,331	05/29/01	Yun			08/18/98
	6,248,602	06/19/01	Bode et al.			11/01/99
	6,252,412	06/26/01	Talbot et al.			01/08/99
	6,263,255	07/17/01	Tan et al.			05/18/98
	6,292,708	09/18/01	Allen et al.			06/11/98
	6,298,274	10/02/01	Inoue			09/01/99
	6,303,395	10/16/01	Nulman			06/01/99
	6,345,315	02/05/02	Mishra			08/12/98
	6,366,934	04/02/02	Cheng et al.			06/02/99

FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	WO 00/79355 A1	12/28/00	WO			X	
	2001-76982	03/23/01	Japan				X
	WO 01/33501 A1	05/10/01	WO			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)	

EXAMINER	DATE CONSIDERED
----------	-----------------

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.